

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

Shigemasa SUGA

Serial No.: 10/579,141

Filed: December 28, 2006

Group Art Unit: 1796

Examiner: Gregory E. Webb

For: CLEANER

**DECLARATION UNDER 37 CFR 1.132**

Honorable Commissioner of Patents and Trademarks  
Alexandria, Virginia. 22313-1450

Sir:

I, Shigeru KAMON, do declare and state as follows.

This is to supplement my previous declaration.

Be shown in the following table 20. APM Cleaning liquid of the same composition as being used in the case of the example of Morinaga et al US6,896,744 was prepared, and pH of solution when adding to this phosphoric acid 1wt% and hydrofluoric acid 1wt%, respectively, was measured. The results are shown in Table 20.

Table 20			
pH when adding Phosphoric acid and hydrofluoric acid 1% in APM Cleaning liquid			
Sample	no complexing agents.	1% addition of phosphoric acid	1% addition of hydrofluoric acid
APM1	10.0	7.1	4.0
APM2	10.5	9.2	4.8
APM3	10.3	8.3	4.4
APM1 Composition:	Solution which mixed 29wt% ammonia water and 31wt% hydrogen peroxide and DIW by 1:2:80, pH 10.		
APM2 Composition:	Solution which mixed 29wt% ammonia water and 31wt% hydrogen peroxide and DIW by 1:2:40, pH 10.5.		
APM3 Composition:	Solution which mixed 29wt% ammonia water and 31wt% hydrogen peroxide and DIW by 1:2:60, pH 10.3.		

Although alkali is slightly indicated to be pH 9.2 with APM2 sample, the removal capability of particle is very low also at this case. Especially when hydrofluoric acid is added with all samples, in order to show acidity and to make pH or more into nine, it turns out that it needs to be extremely made low concentration.

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Date

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Shigeru KAMON